

IN THE CLAIMS:

1. (Currently Amended) A manufacturing method of a display device comprising ~~including~~ the step of:

forming a wiring by partially ~~forming~~ etching a conductor film over a substrate by ~~use of~~ discharging a reactive gas from a plasma treatment means having one set of electrodes ~~an electrode~~ for generating plasma at a pressure of 5 to 800 Torr.

2. (Currently Amended) A manufacturing method of a display device comprising ~~including~~ the step of:

forming a wiring by partially ~~forming~~ etching a conductor film over a substrate by ~~use of~~ discharging a reactive gas from a plasma treatment means having a plurality of sets of electrodes for generating plasma at a pressure of 5 to 800 Torr.

3. (Canceled)

4. (Currently Amended) A manufacturing method of a display device comprising the steps of:

~~partially~~ forming a conductor film over a substrate ~~at a pressure of 5 to 800 Torr by~~ ~~use of first plasma treatment means having a plurality of electrodes;~~

forming a resist mask over ~~on~~ the conductor film; and

partially etching the conductor film at a pressure of 5 to 800 Torr by ~~use of~~ discharging a reactive gas from a ~~second~~ plasma treatment means having one set of electrodes with the resist mask as a mask and forming a wiring.

5. (Currently Amended) A manufacturing method of a display device comprising the steps of:

~~partially~~ forming a conductor film over a substrate ~~at a pressure of 5 to 800 Torr by~~ ~~use of first plasma treatment means;~~

forming a resist mask over ~~on~~ the conductor film; and

partially etching the conductor film at a pressure of 5 to 800 Torr by ~~use of~~
discharging a reactive gas from a second plasma treatment means having a plurality of sets of
electrodes with the resist mask as a mask and forming a wiring.

6. (Currently Amended) The manufacturing method of the display device according
to any of claims 1, 2, 4 and 5 ~~1 to 5~~, wherein the substrate has a size of 1,000 x 1,200 mm² or
more.

7. (Currently Amended) The manufacturing method of the display device according
to any of claims 1, 2, 4 and 5 ~~1 to 5~~, wherein the plasma treatment means scans the substrate
in one direction.

8. (Currently Amended) The manufacturing method of the display device according
to any of claims 1, 2, 4 and 5 ~~1 to 5~~, wherein the plasma treatment means alternately scans the
substrate in a row direction and in a column direction.

9. (Currently Amended) The manufacturing method of the display device according
to any of claims 4 and 5 ~~3 to 5~~, wherein the resist mask is formed by use of liquid droplet
jetting means.

10. – 11. (Canceled)